

## PATENT

Atty. Dkt. No. AMAT/4213.P1/MASK/MASK-ETCH/ARNOLD S

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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JUN 17 2004

In re Application of:  
Buie, et al.

Serial No.: 10/024,958

Confirmation No.: 3439

Filed: December 18, 2001

**For: Etch Process Photolithographic  
Reticle Manufacturing with  
Improved Etch Bias**

www.ck12.org

Group Art Unit: 1765

# OFFICIAL

Examiner: Kin-Chan Chen

MAIL STOP AF  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

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6/17/04  
Date

Kent R. Zuber  
Signature

Dear Sir:

**RESPONSE TO FINAL OFFICE ACTION DATED MARCH 18, 2004**

In response to the Final Office Action dated March 18, 2004, having a shortened statutory period for response set to expire on June 18, 2004, please enter this response and reconsider the claims pending in the application for reasons discussed below. Although Applicant believes that no additional fees are due in connection with this response, the Commissioner is hereby authorized to charge counsel's Deposit Account No. 20-0782/AMAT/4213.P1/KMT, for any fees, including extension of time fees or excess claim fees, required to make this response timely and acceptable to the Office.

**Amendments to the Claims** are reflected in the listing of claims which begins on page 2 of this paper. **Remarks** begin on page 7 of this paper.

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**JUN 17 2004**

**DATE:** June 17, 2004  
**FILE NO:** AMAT/4213.P1/MASK/MASK-ETCH/ARNOLD S  
**TO:** Examiner: Kin-Chan Chen  
**FAX NO:** 703-872-9306  
**COMPANY:** USPTO  
**FROM:** Brian K. Hrna  
**PAGE(S) with cover:** 11  
**ORIGINAL TO FOLLOW?** ☐ YES ☒ NO

**OFFICIAL****RESPONSE TO FINAL OFFICE ACTION DATED MARCH 18, 2004**

**TITLE:** Etch Process Photolithographic Reticle Manufacturing with Improved Etch Bias  
**U.S. SERIAL NO.:** 10/024,958  
**FILING DATE:** December 18, 2001  
**INVENTOR:** Buie, et al.  
**EXAMINER:** Kin-Chan Chen  
**GROUP ART UNIT:** 1765  
**CONFIRMATION NO.:** 3439

**CONFIDENTIALITY NOTE**

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